

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) A method for fabricating a patterned thin film, comprising the steps of:
preparing a base,
forming a resist mask on said base,
forming a thin film via said resist mask to form a patterned thin film,
coating an organic resin with an optical crosslinking agent therein to form an organic resin layer over said resist mask and said patterned thin film,
crosslinking said organic resin layer, and
removing said resist mask and said organic resin layer.
2. (Original) The fabricating method as defined in claim 1, wherein said resist mask is composed of a bottom resist layer with undercuts and a top resist layer, whereby the surface area of said top resist layer is set larger than the surface area of said bottom resist layer.
3. (Original) The fabricating method as defined in claim 2, wherein said bottom resist layer is made of polymethylglutarimide (PMGI).
4. (Original) The fabricating method as defined in claim 3, wherein said top resist layer is made of a phenol-based hydroxyl group-containing resist.
5. (Original) The fabricating method as defined in claim 1, wherein said patterned thin film is formed by means of lift off, dry etching or the combination thereof.

6. (Original) The fabricating method as defined in claim 1, wherein said resist mask and said organic resin layer are removed through immersion in an organic solvent and vibration therein.
7. (Original) The fabricating method as defined in claim 1, wherein said resist mask and said organic resin layer are removed through irradiation of ultrasonic wave.
8. (Original) The fabricating method as defined in claim 1, wherein said patterned thin film includes no flash.
9. (Currently Amended) A micro device comprising a patterned thin film without flashes which is formed by a fabricating method as defined in ~~any one of claims 1-7.~~ claim 1.
10. (Currently Amended) A thin film magnetic head comprising a patterned thin film without flashes which is formed by a fabricating method as defined in ~~any one of claims 1-7.~~ claim 1.
11. (Original) The thin film magnetic head as defined in claim 10, comprising a magnetoresistive effective element which is composed of said patterned thin film.